Welcome
42nd European CMP Users Group Meeting
Thursday, April 15, 2021; 14:00 – 18:00
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Some Statistics:

> 295 registrations for CMP and WET UGM
  6 presentations CMP
  9 presentations Wet
  17 sponsors
CMP Processes: Session 1
Session Chair: Catharina Rudolph, Fraunhofer ASSID, Dresden, Germany

14:00 Welcome
Gerfried Zwicker
zwickerconsult, Berlin, Germany

14:10 Ge CMP Defect Reduction by Using Soft Polishing Pad
Sara Manghooli, Patrick Ong, Shuo Kang, Andre Moet, and Billy Merry
imec, Leuven, Belgium

14:35 Technical Company Presentation
Romain Ridremont and Xavier Buch
JSRmicro BV, Leuven, Belgium

15:00 Soft Pad Conditioning
Walter Schoenholfen
3M Deutschland GmbH, Neuss, Germany

15:25 Coffee Break
CMP Processes: Session 2

Session Chair: Benjamin Steible, Fraunhofer ISIT, Itzehoe, Germany

16:00 Novel Filtration Technology for Large Particle and Fine Particle Removal from Slurries
Bradley Wood
Entegris Inc, Billerica, MA, USA

16:25 Barrier CMP Process Characterization with Diamonex® CVD Diamond Coated Discs
Yasa Sampurno, Dave Slutz, and Ara Philipossian
Araca, Tucson, AZ, USA / Diamonex, Allentown, PA, USA

16:50 Effect of Supramolecular Cleaning Chemistries Using Brush and Megasonic Post-CMP Cleaning Processes
Jason Keleher
Lewis University, Romeoville, IL, USA

17:15 CMP Session Final Remarks
Gernfried Zwicker
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Coffee Break
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Thank You:
- speakers
- session chairs
- attendees
- sponsors

Next Meeting: October 2021, hopefully face-to-face

CMPUGM U.S.A.:
- NCCAVS - CMPUG Spring Virtual Meeting
  April 22, 2021, 1:00 – 6:00 pm CDT

CAMP Meeting: August 2021